



**COST**

## **COST Action MP1307**

***Stable Next Generation Photovoltaics: Unraveling Degradation Mechanisms of Organic Solar Cells by Complementary Characterization Techniques.***

**2<sup>nd</sup> MC Meeting and 1<sup>st</sup> WG Meeting**

**Harald Hoppe**

**WP4: Non-destructive Characterization**

**Hotel Condes de Barcelona, Barcelona, Spain. 8<sup>th</sup> -9<sup>th</sup> October, 2014**



# Sample & Characterization issues

- Samples are divided as  
Industrial (I), Modules (M), Cells (C) and Films (F)
- Contacts need to be of robust nature (!!!) – for repeated contacting and long-term measurements
- Depending on sample type, YOUR characterization technique might be either NON-DESTRUCTIVE or DESTRUCTIVE
- Why? Because, if we need to open a sealed device, the characterization following is DESTRUCTIVE



# How to choose participation?

Point system(???):

- Your method is useful for the specific goal of an experiment
  - You can provide more than one method at the same time
  - Logistics remains doable
  - Experiment remains conductible
- 
- In general: the lowest complexity of experiments will be preferred that can provide a critical amount of information
  - Sorry, no extrapoints... ;-)



**Method Classification:**  
**Non-**  
**Destructive?**

# Solar Modules and Solar Cells

## Non-destructive

- Raman
- UV-Vis
- PL/EL
- Ellipsometry
- IS
- IV
- EQE
- CELIV
- LBIC
- PLI/ELI
- DLIT/ILIT
- OM
- Modelling & Simulation

## Destructive

- AFM
- STM
- SEM
- XPS
- STXM
- NEXAFS
- SAXS
- ERDA
- He ion microscopy
- SIMS
- RBS
- GISAXS
- GIWAXS

Not applicable

RBS, TEM, ET, FTIR, DSC, TGA, DSC

# Layer Stack Subsystem

## Non-destructive

- Raman
- PL
- Ellipsometry
- PLI
- OM
- AFM
- STM
- SEM
- TEM
- FTIR/IR
- DSC
- ILIT
- XPS (surface)
- Modelling & Simulation
- SHIM
- STXM
- NEXAFS
- GISAXS
- GIWAXS
- SAXS
- ET

## Destructive

- XPS (depth)
- SIMS
- ERDA

Not applicable

EL, IS, IV, CELIV, EQE, ELI, DLIT, LBIC, RBS, TGA

# Films

## Non-destructive

- Raman
- PL
- Ellipsometry
- PLI
- OM
- AFM
- STM
- SEM
- TEM
- FTIR/IR
- DSC
- ILIT
- XPS (surface)
- Modelling & Simulation
- SHIM
- STXM
- NEXAFS
- GISAXS
- GIWAXS
- SAXS
- ET

## Destructive

- XPS (depth)
- SIMS
- ERDA
- TGA

Not applicable

EL, IS, IV, CELIV, EQE, ELI, DLIT/ILIT, LBIC, RBS

- SHIM: scanning helium ion microscopy
- IS: impedance spectroscopy
- STXM: scanning transmission x-ray microscopy
- NEXAFS: near-edge x-ray absorption fine structure
- SIMS: secondary ion mass spectrometry
- OM: optical microscopy
- RBS: Rutherford backscattering spectrometry
- ERDA: elastic recoil detection analysis
- ET: electron tomography
- DSC: differential scanning calorimetry
- TGA: thermal gravimetric analysis
- CELIV: charge extraction by linearly increasing voltage
- GIS(W)AXS: grazing-incidence small(wide)-angle x-ray scattering





ecocost

n-d. Characterization:  
**Result of Survey**



# Next steps

- Please check your assignment
- We will update the general n-d characterization list
- We might add a column for modules
- We might consider to build up a small database for example characterizations

The logo for eccc cost features a stylized 'e' on the left, composed of a grey outline with a horizontal bar on its left side. This bar is divided into four colored segments: dark blue, purple, black, and orange. To the right of the 'e' is the text 'ccc cost' in a grey, sans-serif font. The 'c's are lowercase, the 'o' is lowercase, and 'st' are lowercase. The 'c's have a square cutout in the middle, and the 'o' is a simple square with a square cutout in the center. The 's' and 't' are also lowercase and have a similar square cutout design.

eccc cost

\_\_\_\_\_